PATENT



Applicants: Schottek et al.

Group Art Unit: 1713

Serial No.: 10/828,814

Docket: 1094-54 N

Filed:

April 21, 2004

Dated: December 30, 2005

For: METALLOCENE LIGANDS, METALLOCENE COMPOUNDS AND

METALLOCENE CATALYSTS, THEIR SYNTHESIS AND THEIR

USE FOR THE POLYMERIZATION OF OLEFINS

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Sir:

Pursuant to Applicant's continuing duty of disclosure, it is respectfully requested that the references listed in the attached form PTO-1449 be considered by the Examiner and made of record in the above-identified application. A copy of each non-U.S. reference is attached hereto.

The citation of the listed items is not a representation that they constitute a complete or exhaustive listing of the relevant art or that the references are prior art. The items listed are submitted in good faith, but are not intended to substitute for the Examiner's search. It is hoped, however, that in addition to apprising the Examiner of these particular items, they will assist in identifying fields of search and in making as full and complete a search as possible.

CERTIFICATE OF MAILING UNDER 37 C.F.R. §1.8(a)

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail, postpaid in an envelope addressed to the: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on December 30, 2005.

Dated: December 30, 2005

Maria Goldman

The listed items were cited by the European Patent Office in a counterpart application, namely Appln. No. PCT/US2005/014340. A copy of the Notification of Transmittal of The International Search Report dated November 17, 2005 is attached hereto.

The filing of this Supplemental Information Disclosure Statement is not an admission that the information cited herein is, or is considered to be, material to patentability as defined in 37 C.F.R. § 1.56(b).

The claims of the application as now presented are believed to patentably distinguish over the prior art and to be in condition for allowance. Early and favorable consideration of the case is respectfully requested.

CERTIFICATION UNDER 37 C.F.R. §1.97(e)(2)

Applicants submit that each item of information contained in the Supplemental Information Disclosure Statement was cited in a communication from a foreign patent office in a counterpart foreign application no more than three months prior to the filing of the Statement.

Respectfully submitted,

Adrian T. Calderone Reg. No. 31,746

Attorney for Applicants

DILWORTH & BARRESE, LLP 333 Earle Ovington Blvd. Uniondale, NY 11553 (516) 228-8484 (516) 228-8516

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Form PTO-1449	FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. 1094-54 N		Sheet 1 of 3		
JAN 0 5 2006 PURPORMATION DISCLOSURE STATEMENT BY APPLICANT Several sheets if necessary)			APPLICANTS Schottek et al.				
			FILING DATE April 21, 2004	GROUP ART UNIT 173			.3
		U.S. P	ATENT DOCUMENTS				
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLAS	S SUBCLASS	FILING	G DATE OPRIATE
	6,184,402	Feb. 6, 2001	Hiroshi et al.				
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		FOREIGN	PATENT DOCUMENTS	l		<u> </u>	
	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	S SUBCLASS	TRANSLATION	
						YES	NO
	WO 03/051943	June 26, 2003	WO			<u> </u>	
	WO 02/14384 A	Feb. 21, 2002	WO				-
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OTHER PRIOR ART (Including Author, Title, Date, Pertinent Pages, Etc.)				
Alt, Helmut G. et al., "ansa-Metallocene complexes of typeself-immobilized catalysts for ethylene polymerization", <i>J. of Organometallic Chemistry</i> , 562(2), 229-253 (1998)				
Guo, Dawei et al., "Molecular modeling on the prediction of silolene-bridged indenyl metallocene catalyst for isotactic polypropylene", J. of Polymer Science, 38(12), 2232-2238 (2000)				

EXAMINER

DATE CONSIDERED

^{*} EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.